# Updates from the SoLID-GEM Chinese Collaboration

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### **SoLID-GEM Chinese Collaboration**

#### **China Institute of Atomic Energy (CIAE)**



#### Lanzhou University

#### Institute of Modern Physics, CAS (IMP)



#### Tsinghua University

Tsinghua University

University of Science and Technology of China (USTC)





#### Lanzhou University



• Recent development on DAQ with APV25 readout

# **DAQ Design and development**

#### Design Diagram





DAQ board

# Comparison with MPD

	New DAQ	MPD
Chip	Xilinx XC5VSX50T: 4.752Mb-RAM	Altera EP1AGX50DF : 2.475Mb-RAM
Protocol	Ethernet 1000Mbps	VME 60Mbps
I/O	HDMI Type A Easy to buy	
Power	low-voltage power supply	

# Backplane board copied from INFN





A A A A A A A A A A A A A A A A A A A	OxFA	Detector ID	Board ID	Work Mode	
	Trigger Number				per trigger : 288B
	Total Trigger Counts				
		Time_dat	ta[63:32]		per trigger : 8,408KB
		Time_da	ta[31:0]		
	Reservel				
	Channel	No_1 Data	Channel N	lo_2 Data	
	Channel	No_3 Data	Channel N	lo_4 Data	4 chips * 30 samples * 320
					rate *2 hours =800GB
	Channel N	lo_125 Data	Channel No	_126 Data	
	Channel N	lo_127 Data	Channel No	_128 Data	Working OK
	02	xFB	Sta	tus	
0=* 	Byte Count				
	Data Format				

Data transmission speed: 120MB/s when writing to memory Reaching the limit of Gigabit Ethernet.

## **Test with a Detector**



3 Alpha sources (Am-241), each illuminating the detector through a slit. Two-dimensional strip readout with 167 channels in each dimension.





#### A typical Alpha signal with 30 samples







- uRWELL R&D
- VMM readout development

# The uRWELL detector

- Micro-Resistive WELL (µRWELL) is a novel sparkprotected Micro-Pattern Gaseous Detector (MPGD) with a single well-type amplification stage
- **Resistive Electrode** • Drift Cathode One-stage WELL pattern . DLC layer: ~0.1 µm -45 MO/ 3mm Suppress discharge • hePreg: 58 µm Better gain uniformity **µRWELL PCB** Compact and high granularity • **Fabrication fast** • Typical structure of µRWELL detector Schematic of µRWELL PCB ( Drift +  $\mu$ RWELL PCB =  $\mu$ RWELL )

**µRWELL PCB**: A stack of "readout PCB / insulating pre-preg / DLC resistive layer / well-type amplification structure"

A critical component of  $\mu$ RWELL PCB is DLC resistive electrode which is used to suppress the discharge.

# **DLC resistive electrode**

 We are collaborating with State Key Laboratory of Solid Lubrication, Lanzhou Institute of Chemical Physics, Chinese Academy of Sciences on DLC production.

#### Sigma/mean=12%



72	62	60
MΩ/□	MΩ/□	MΩ/□
64	57	63
MΩ/⊡	MΩ/⊡	MΩ/⊡
71	59	66
MΩ/⊡	MΩ/□	MΩ/□

a DLC sample of 15cm  $\times$  15cm, resistivity uniformity:  $\pm$  12%



# New sputtering system



A New sputtering system (Hauzer 850) is ready to make larger area DLC samples.

Chamber size: Φ800mm×900mm Best Sample size (up to): 500mm×500mm (Rigid substrate), 500mm × 1900mm (Flexible substrate)

# **2-D** $\mu$ **RWELL PCB with DLC**

#### A 2-D $\mu RWELL$ PCB with 15cm $\times$ 15cm DLC was designed and fabricated. The DLC was made in China

#### µRWELL PCB

- Sensitive area: 10cm × 10cm divided into 4 sectors
- Well pitch: 140 μm
- Pre\_preg (50 μm) isolate the DLC electrode from readout strip
- 2-D readout strip
- Pitch: 400 μm
- Top layer: 80 μm
- Bottom layer: 350 μm
- Insulate thickness: 50 μm
- Readout strip channel: 1024



All the readout strips are connected to 4 HIROSE (for laboratory test) / PANASONIC (for beam test) connectors.



## Performance



# **R&D on high-rate uRWELL**

- High rate uRWELL aiming for > ~ 1 MHz/cm2
- Collaborating with G.Bencivenni from INFN
- Two Approaches
  - Double-resistive layer
  - Conductive-Dashed Grid

# **Double-resistive layer**

Reduce the path of the current on the DLC surface by implementing a matrix of conductive vias connecting two stacked resistive layers. A second matrix vias connects the second resistive layer to ground through the readout electrodes.



From G.Bencivenni, The "MPGD Stability" workshop, 21-June-2018

The engineering/industrialization of the double-resistive layer is difficult due to the manufacturing of the conductive vias on kapton foil. This solution was abandoned.

# **Conductive-Dashed Grid**

The copper clad on the DLC is etched to dash strips and grounded at every a few mm. The charge collected on the DLC can be quickly released via the grounded copper strips. **New combined structure (Cu/DLC/APICAL/Cu) is required to make high-rate µRWELL PCB.** 



Technique for depositing copper on DLC needs to be developed.

This work is supported by a RD51 common project: DLC based electrodes for future resistive MPGDs.

# **RD51 Common Project**

#### DLC based electrodes for future resistive MPGDs

name: Yi Zhou **Contact person:** address: Jinzhai Road No.96, Hefei, Anhui, P.R.China, 230026 telephone number: +86-551-63607940 CERN e-mail: zhouvi@mail.ustc.edu.cn Factors affect DLC in Detector fabricatio 1. State Key Laboratory of Particle Detection and Electronics, **RD51 Institutes:** University of Science and Technology of China, contact person: Yi Zhou e-mail: zhouyi@mail.ustc.edu.cn LICP USTC KOBE 2. Kobe University, Production of large Small DLC + Cu contact person: Atsuhiko Ochi Theoretical calcula Size DLC + Cu foils and simulation foils production e-mail: ochi@kobe-u.ac.jp 3. CERN contact person: Rui de Oliveira e-mail: Rui.de.Oliveira@cern.ch CERN Detector Production 4. Laboratori Nazionali di Frascati dell'INFN with DLC foils contact person: Giovanni Bencivenni e-mail: Giovanni.Bencivenni@lnf.infn.it **USTC** is organizing this project. Ext. Collaborators: 1. State Key Laboratory of Solid Lubrication, Lanzhou Institute of Chemical Physics, Chinese Academy of Science contact person: Lunlin Shang e-mail: shangll@licp.cas.cn

DLC based electrodes for future resistive MPGDs

Title of project:

LNF-INFN

Long-tern stability

and aging test

## **Progress on copper coated DLC**

#### Deposit copper on DLC by magnetron sputtering was developed.

- 1. Deposit DLC on APICAL/Cu substrate
- 2. Deposit copper on DLC/APICAL/Cu substrate

Good adhesion between DLC and copper.

The thickness of copper can be adjusted from 1  $\mu m$  to 5  $\mu m.$ 

Several substrates have been tried to make the Conductive-Dashed Grid  $\mu$ RWELL PCB.

# <image>

# **Conductive-Dashed** µRWELL PCB

- 1. Cu/DLC/APICAL/Cu substrate
- 2. Etch the copper clad on DLC to dash strip
- 3. Glue the readout PCB and substrate
- 4. Etch the copper clad on the APICAL
- 5. Etch APICAL

Several high-rate  $\mu RWELL$  prototypes have been fabricated and tested at PSI.





## Performance



#### Preliminary result from Giovanni

#### Conductive-Dashed Grid: SG2++

The resistive electrode of SG2++ was made by a new combined structure (Cu/DLC/APICAL/Cu) from USTC.

- Efficiency: 97% @SG2++
- Rate capability: Gain drop 20% @10 MHz/cm<sup>2</sup>

# Design of a VMM-based FEE card

- Two 140-pin Hirose connector, four VMM chips → 256 channels
- 64 4-channel ESDs (SP3004) for input protection
- HDMI with four high-speed Differential pairs (~340Mbps bandwidth) for output.



# Design of a DAQ board

- 8 HDMIs (8 × 256 channels), scalable.
- Receive and fan out the clock and trigger signal
- Both auto-trigger and external trigger available.



# Integration and test



#### FEE noise:

Standalone: <u>Vp</u>-p<=4mV, Vrms<=800uV With detector: <u>Vp</u>-p<=20mV, <u>Vrms</u><=3mV

#### Timing resolution: RMS = ~0.5ns

Channel tdo Distribution Graph 2



#### A Micromegas detector



# Signal with cosmic rays and X-rays

#### Testing with cosmic rays and 5.9keV x-rays



#### cosmic ray signal (anode)



#### X-ray signal (anode)

